

## Description

# METHOD FOR MONITORING QUALITY OF AN INSULATION LAYER

### CROSS REFERENCE TO RELATED APPLICATIONS

[0001] This is a continuation-in-part of U.S. Application No. 10/065,432, filed Oct 17, 2002, and which is included herein by reference.

### BACKGROUND OF INVENTION

[0002] 1. Field of the Invention

[0003] The present invention provides a method for monitoring quality of an insulation layer, and more particularly, relates to a method for quickly monitoring the stress-induced degradation of an insulation layer in different structures with wafer acceptance testing (WAT) equipment.

[0004] 2. Description of the Prior Art

[0005] In today's electronics industry, semiconductor devices make extensive use of the unique characteristics of semi-